

CLAIMS

1. A sputtering target material, wherein a portion to be used for sputtering of the sputtering target material is subjected to a friction stir processing.
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2. The sputtering target material according to claim 1, wherein the sputtering target material is made of an aluminum alloy.
3. The sputtering target material according to claim 2, wherein the
10 aluminum alloy comprises carbon.
4. The sputtering target material according to claim 2 or 3, comprising any one or more elements selected from nickel, cobalt and iron.
- 15 5. The sputtering target material according to any one of claims 1 to 4, wherein the sputtering target material is a sintered material or a cast material.